

日本の 1005 Web に対し、 1005 Web には 2005 Web に

It has now been found that a relatively simple and effective process is provided for chemically bonding a <u>thermoset</u> resin to a poly-p-xylylene substrate by exposing the poly-p-xylylene to a cold plasma in a confined region for a period of time sufficient to chemically modify the <u>surface</u> of the poly-p-xylylene exposed to the cold plasma, depositing an uncured liquid <u>thermosetting</u> resin over the chemically modified poly-p-xylylene <u>surface</u>; and then heating the <u>thermosetting</u> resin and poly-p-xylylene at a temperature and time sufficient to both <u>cure the thermosetting</u> resin into a solid <u>thermoset</u> resin and chemically bond the chemically modified <u>surface</u> of the poly-p-xylylene to the <u>thermoset</u> resin in situ.

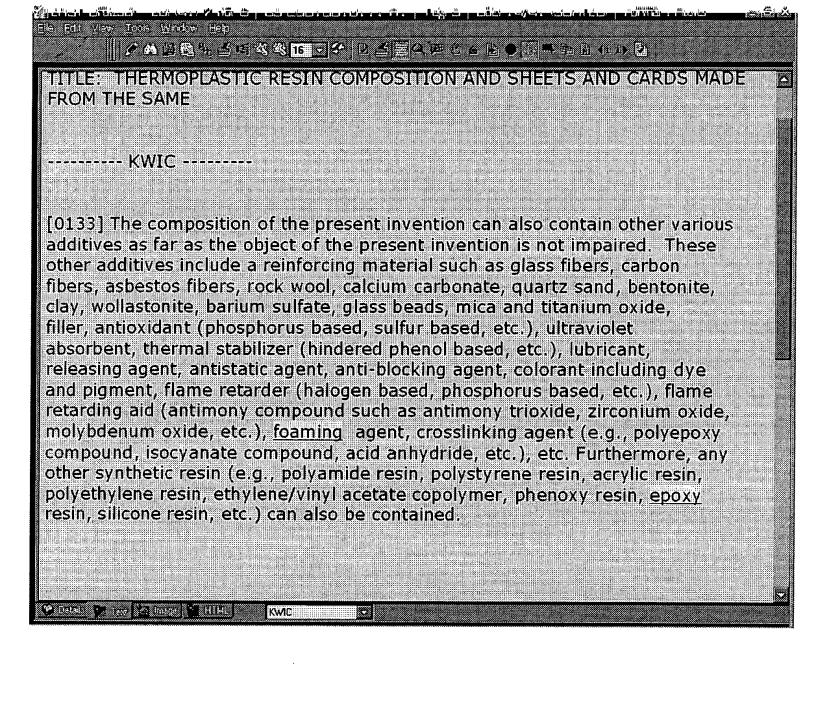
Detailed Description Text - DETX (2):

The basic process of the present invention may be more explicitly defined as a process for chemically bonding a <u>thermoset</u> resin to a poly-p-xylylene substrate comprising: providing a cold plasma within a confined region evacuated to a pressure lower than about 100 torr; exposing at least one <u>surface</u> of the poly-p-xylylene substrate directly to said plasma within said region for a period of time sufficient to incorporate oxygen-containing functional groups thereinto which contain active hydrogen atoms; depositing an uncured liquid <u>thermosetting</u> resin capable of chemically reacting with active hydrogen atoms over the plasma treated poly-p-xylylene <u>surface</u>; and heating the <u>thermosetting</u> resin and poly-p-xylylene at a temperature at which the thermosetting resin

[0014] The present invention provides a method for manufacturing a semiconductor package including the steps of: forming at least one curable resin layer: forming a package <u>substrate</u> having at least one cavity, the cavity having a top opening and receiving therein a semiconductor chip; placing the package <u>substrate</u> on the curable resin layer, with the top opening being closed by the curable resin layer; and <u>curing</u> the curable resin layer to form a cap member encapsulating the semiconductor chip in the cavity.

[0047] Thereafter, the curable resin layer 15a is heated from the bottom of the mold die 22 for two to three hours at a temperature of 200 degrees C. or below, preferably between 120 and 150 degrees C., for a thermosetting process. This provides the encapsulation structure shown in FIG. 10, without using an adhesive, wherein the curable resin layer 15a adhered onto the wall <u>substrate</u> 12 during the <u>curing</u> process absorbs a pressure rise due to the expansion of the air inside the cavity 13.

[0048] The curable resin layer 15a has a concave inner surface at each opening due to the pressure applied at the initial stage of the heating at which the curable resin layer 15a has a lower viscosity. In the encapsulation structure shown in FIG. 10, the top of the cured resin 15 adheres at the bottom of the wall substrate 12 during the curing step, whereby the cured resin 15 constitutes the cap member for each cavity 13. The bottom of the cured resin that have been presented as the cured resin to the



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DOCUMENT-IDENTIFIER: US 20020142167 A1	
TITLE: Underfill material for COF mounting and electronic components	
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[0048] If desired, the <u>epoxy</u> resin composition can further contain appropriate amounts of various anti- <u>foaming</u> agents, silane coupling agents, pigments, and the like, particularly carbon black.	
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The finality of the or mailed ____ is withdrawn in view of the new grounds of agreedion below.

